

	Search Text	DBs	Time Stamp
1	(etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/09 15:59
2	PR or photoresist or resist or ARC or (anti-reflecti ve adj coating) or (antireflectiv e adj coating) or (anti adj reflective adj coating)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/09 16:01
3	plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/09 16:02
4	singl\$4 or complet\$4 or "one step" or "single step"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/09 16:03
5	((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") same (PR or photoresist or resist or ARC or (anti-reflecti ve adj coating) or (antireflectiv e adj coating) or (anti adj reflective adj coating)) same plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/09 16:05

	Search Text	DBs	Time Stamp
6	((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") near4 (PR or photoresist or resist or ARC or (anti-reflecti ve adj coating) or (antireflectiv e adj coating) or (anti adj reflective adj coating)) near8 plasma near8 (singl\$4 or complet\$4 or "one step" or "single step")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/09 16:05
7	((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") near8 (PR or photoresist or resist or ARC or (anti-reflecti ve adj coating) or (antireflectiv e adj coating) or (anti adj reflective adj coating)) near8 plasma near8 (singl\$4 or complet\$4 or "one step" or "single step")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/09 16:07

	Search Text	DBs	Time Stamp
8	((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") near4 (PR or photoresist or resist or ARC or (anti-reflecti ve adj coating) or (antireflectiv e adj coating) or (anti adj reflective adj coating)) near8 plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 09:42
9	((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") same (PR or photoresist or resist or ARC or (anti-reflecti ve adj coating) or (antireflectiv e adj coating) or (anti adj reflective adj coating)) same plasma same (singl\$4 or complet\$4 or "one step" or "single step")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 09:43

	Search Text	DBs	Time Stamp
10	((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") same (PR or photoresist or resist or ARC or (anti-reflecti ve adj coating) or (antireflectiv e adj coating) or (anti adj reflective adj coating)) same plasma same (singl\$4 or complet\$4 or "one step" or "single step")) not (((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") near4 (PR or photoresist or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 09:43
11	(438/717).CCLS .	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 10:44
12	(438/697).CCLS .	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 11:39
13	(438/694).CCLS .	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 13:46
14	(438/695).CCLS .	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 13:50
15	(438/709).CCLS .	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 14:28

	Search Text	DBs	Time Stamp
16	(438/738).CCLS .	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/10 15:33

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L5	19342	(etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask"	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 15:59
2	BRS	L6	783392	PR or photoresist or resist or ARC or (anti-reflective adj coating) or (antireflective adj coating) or (anti adj reflective adj coating)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 16:01
3	BRS	L7	356204	plasma	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 16:02
4	BRS	L9	379232 9	singl\$4 or complet\$4 or "one step" or "single step"	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 16:03
5	BRS	L12	127	5 near4 6 near8 7	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 16:04

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L15	372	5 same 6 same 7 same 9	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 16:05
7	BRS	L16	1711	5 same 6 same 7	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 16:05
8	BRS	L13	5	5 near4 6 near8 7 near8 9	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 16:05
9	BRS	L14	12	5 near8 6 near8 7 near8 9	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/09 16:07

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	127	((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") near4 (PR or photoresist or resist or ARC or (anti-reflective adj coating) or (antireflective adj coating) or (anti adj reflective adj coating)) near8 plasma	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/10 09:42
2	BRS	L2	372	((etch adj stop\$4) or etchstop\$4 or (hard adj mask) or "hard mask") same (PR or photoresist or resist or ARC or (anti-reflective adj coating) or (antireflective adj coating) or (anti adj reflective adj coating)) same plasma same (singl\$4 or complet\$4 or "one step" or "single step")	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/10 09:43
3	BRS	L3	346	2 not 1	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/11/10 09:43